

忠 茲

藤 正 司

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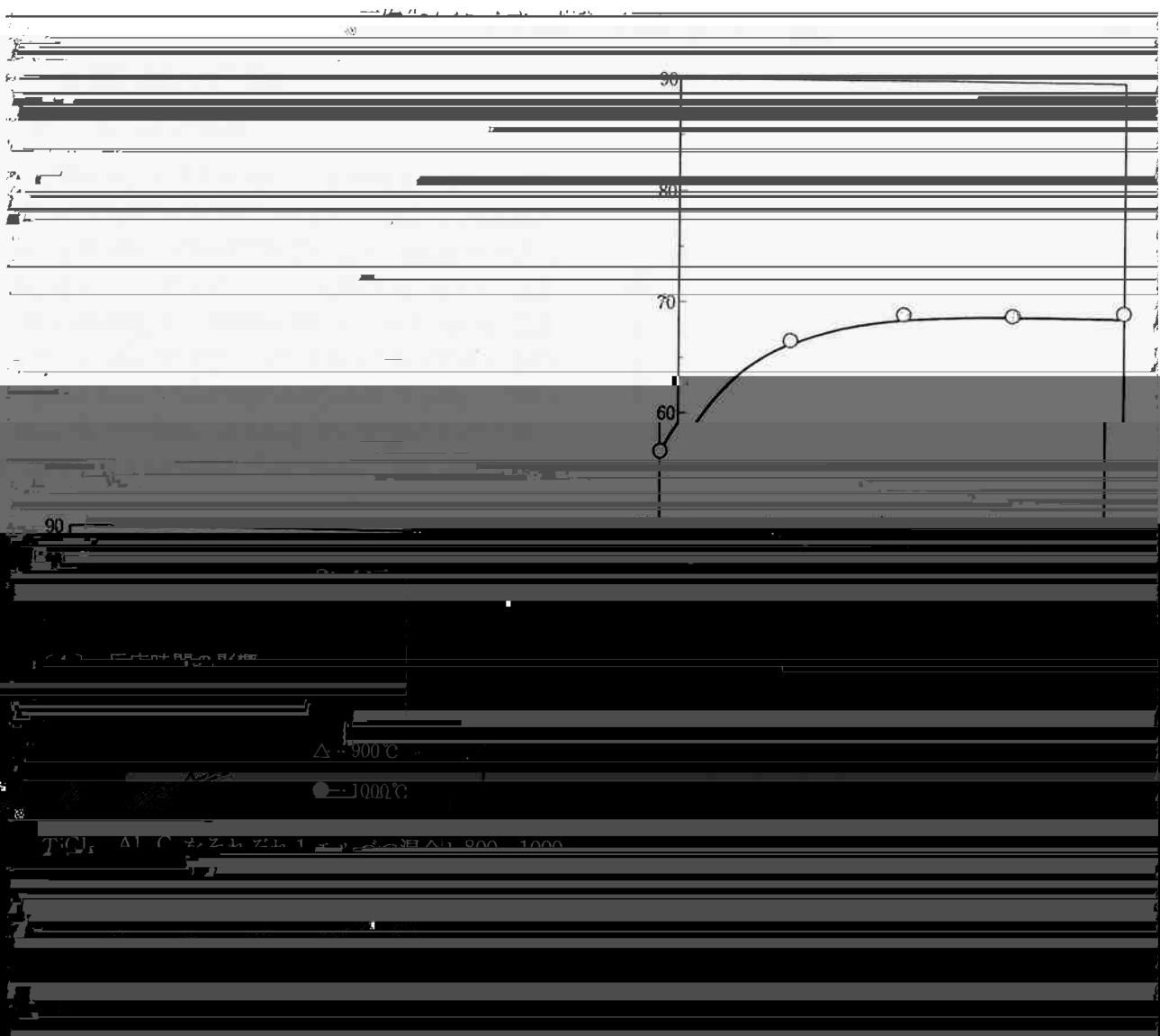
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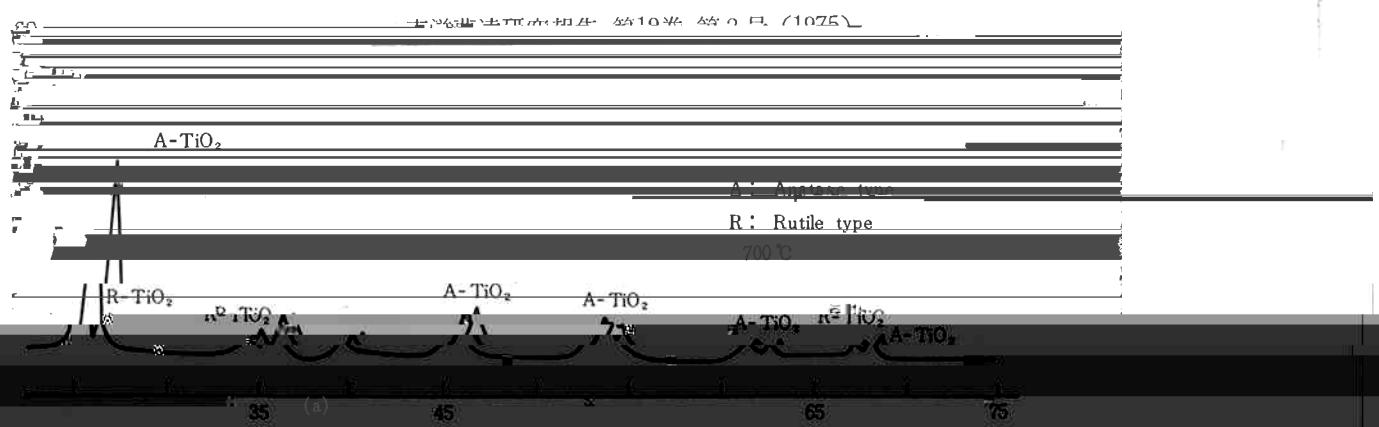
Vacuum pump

Fig. 1 Apparatus for annealing of TiC.

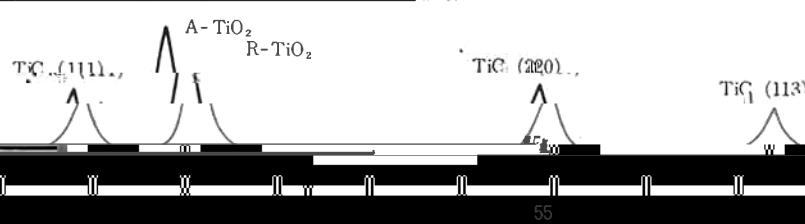


○ Δt 温度範囲で炭化層下にセメント層の形成による影響

Ryukawa, T., 1991, Preparation of Al_2O_3 by the

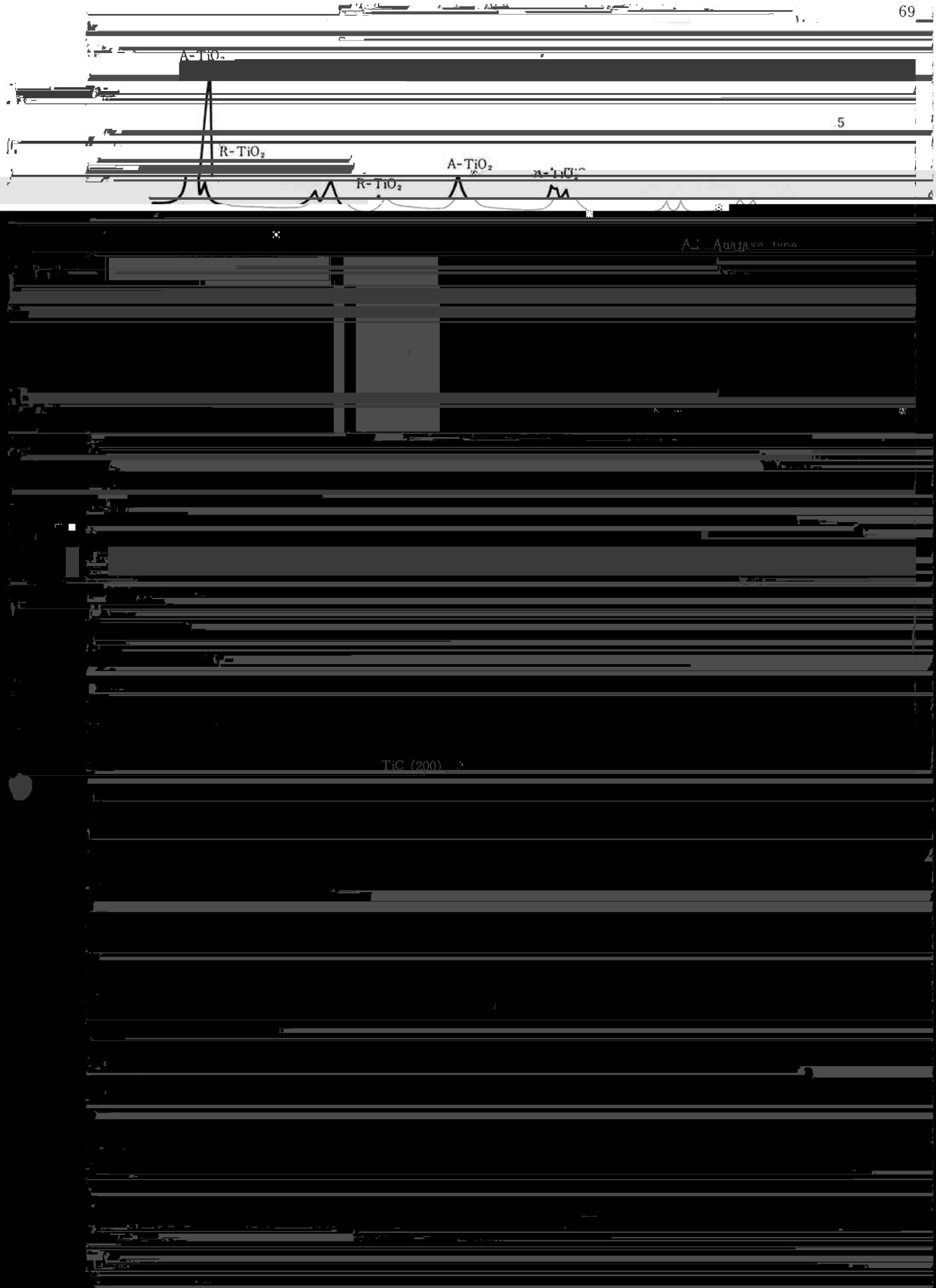


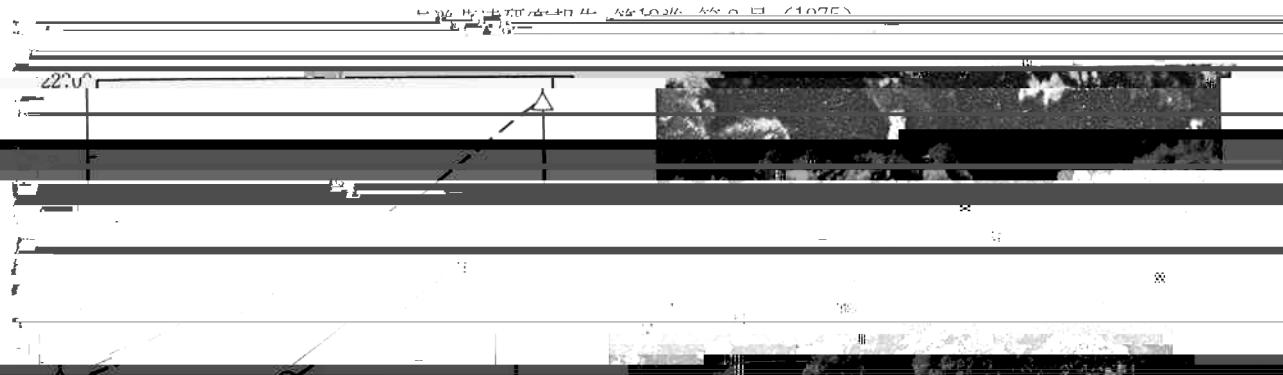
(b)



$\theta / ^\circ (0.01^\circ)$

Fig. A X-ray patterns of products at various temperature.





○— 1000 °C

△— 1100 °C



Fig. 7 The relation between Carbon molar ratio to TiCl_3 and Total Carbon.
(holding time : 30 min.)

■ 5. 総括

○— 1000 °C

Reaction temperature : 1000°C

△— 1100 °C